

Appl. No. 09/218,997  
Amdt. Dated: September 19, 2003  
Reply to Office Action of June 19, 2003

Attorney Docket No. 8565D-7213 (81839.0077)  
Customer No. 26021

**Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of Claims:**

---

1. (Currently Amended): A storage water used for storage of a silicon wafer in water, wherein the storage water is ultra pure water containing Cu at a concentration of 0.01 ppb or less, a chelating agent and a surfactant, and used in the form of pit water.

2-3. (Cancelled)

E/ 4. (Currently Amended): A method of storing a silicon wafer in water, comprising the steps of preparing storage water, which is ultra pure water containing Cu at a concentration of 0.01 ppb or less, a chelating agent and a surfactant, and storing a silicon wafer in the prepared storage water in the form of pit water in a waiting period between steps in a silicon wafer production process.

5. (Cancelled)

6. (Previously Presented): A method of storing a silicon wafer in water according to Claim 4, wherein the step of storing a silicon wafer includes providing a silicon wafer having a hydrophobic surface.

7. (Cancelled)

8. (Previously Presented): A method of storing a silicon wafer in water according to Claim 4, wherein the step of storing the silicon wafer comprises storing the silicon wafer immediately after polishing.

9. (Cancelled)

10. (Previously Presented): A method of storing a silicon wafer in water according to Claim 6, wherein the step of storing the silicon wafer comprises storing the silicon wafer immediately after polishing.

11-13. (Cancelled)

14. (Currently Amended): A method of storing a silicon wafer in a storage solution according to Claim ~~12~~ 4, wherein the step of preparing water or a chemical solution includes providing an alkaline solution as the chemical solution containing a chelating agent.

15. (Currently Amended): A method of storing a silicon wafer in a storage solution according to Claim ~~13~~ 6, wherein the step of preparing water or a chemical solution includes providing an alkaline solution as the chemical solution containing a chelating agent.

16-18. (Cancelled)

19. (Currently Amended): A method of storing a silicon wafer in a storage solution according to Claim ~~12~~ 4, wherein the step of preparing water or a chemical solution includes preparing water or a chemical solution containing a chelating agent having a chelate compound production performance not lower than that of NTA.

20. (Currently Amended): A method of storing a silicon wafer in a storage solution according to Claim ~~12~~ 4, wherein the step of preparing water or a chemical solution includes preparing water or a chemical solution containing a

Appl. No. 09/218,997

Attorney Docket No. 8565D-7213 (81839.0077)

Amdt. Dated: September 19, 2003

Customer No. 26021

Reply to Office Action of June 19, 2003

chelating agent selected from the group consisting of NTA, EDTA, DTPA, CyDTA, salts thereof, and a mixture thereof.

21. (Currently Amended) A regulating method of a storage water used for storage of a silicon wafer in water, wherein the concentration of Cu in the storage water, which is ultra pure water containing a chelating agent and a surfactant, is regulated to 0.01 ppb or less in the form of pit water.

22-25. (Cancelled)